

L Number	Hits	Search Text	DB	Time stamp
1	1447	back with substrate with mask	USPAT;	2003/10/29 14:23
2	70890	438/\$.ccls.	US-PGPUB	2003/10/29 14:23
3	578	(back with substrate with mask) and 438/\$.ccls.	USPAT;	2003/10/29 14:23
4	204502	@ad>20020214 or @rlad>20020214	US-PGPUB	2003/10/29 14:23
5	71	((back with substrate with mask) and 438/\$.ccls.) and (@ad>20020214 or @rlad>20020214)	USPAT;	2003/10/29 14:25
6	15184	LED and mask	US-PGPUB	2003/10/29 14:25
7	4686	mask with (stretch\$3 or align\$3) with (substrate or wafer)	USPAT;	2003/10/29 14:50
8	346	(Li:D and mask) and (mask with (stretch\$3 or align\$3) with (substrate or wafer))	US-PGPUB	2003/10/29 14:26
10	19	"radio frequency identification circuit"	USPAT;	2003/10/29 14:35
11	10653	(mask with (stretch\$3 or align\$3) with (substrate or wafer)) nad "radio frequency identification circuit"	US-PGPUB	2003/10/29 14:26
12	1	(mask with (stretch\$3 or align\$3) with (substrate or wafer)) and "radio frequency identification circuit"	USPAT;	2003/10/29 14:26
13	1	"radio frequency identification circuit" and mask	US-PGPUB	2003/10/29 14:27
9	295	((LED and mask) and (mask with (stretch\$3 or align\$3) with (substrate or wafer))) not (@ad>20020214 or @rlad>20020214)	USPAT;	2003/10/29 14:28
14	5438	"light emitting diode" and mask	US-PGPUB	2003/10/29 14:29
15	131	(mask with (stretch\$3 or align\$3) with (substrate or wafer)) and ("light emitting diode" and mask)	USPAT;	2003/10/29 14:29
16	119	((mask with (stretch\$3 or align\$3) with (substrate or wafer)) and ("light emitting diode" and mask)) not (@ad>20020214 or @rlad>20020214)	US-PGPUB	2003/10/29 14:29
17	175	"radio frequency identification" and mask	USPAT;	2003/10/29 14:37
18	8	438/\$.ccls. and ("radio frequency identification" and mask)	US-PGPUB	2003/10/29 14:35
19	6	(438/\$.ccls. and ("radio frequency identification" and mask)) not (@ad>20020214 or @rlad>20020214)	USPAT;	2003/10/29 14:36
20	5	"radio frequency identification" and (mask with (stretch\$3 or align\$3) with (substrate or wafer))	US-PGPUB	2003/10/29 14:37
21	4	("radio frequency identification" and (mask with (stretch\$3 or align\$3) with (substrate or wafer))) not (@ad>20020214 or @rlad>20020214)	USPAT;	2003/10/29 14:37
24	7247	mask and (stretch\$3 or align\$3) and (substrate or wafer)	EPO; JPO;	2003/10/29 14:51
25	918869	semiconductor or "intergrated circuit"	DERWENT	2003/10/29 14:51
28	0	(mask and (stretch\$3 or align\$3) and (substrate or wafer)) and (semiconductor or "intergrated circuit")	EPO; JPO;	2003/10/29 15:07
29	3909	(mask and (stretch\$3 or align\$3) and (substrate or wafer)) and (semiconductor or "intergrated circuit")	DERWENT	2003/10/29 15:07
-	374	438/401.ccls.	USPAT;	2003/10/28 14:00
-	74	438/401.ccls. and (mask with (stretch\$3 or align\$3) with (substrate or wafer))	US-PGPUB	2003/10/28 14:01
-	71	(438/401.ccls. and (mask with (stretch\$3 or align\$3) with (substrate or wafer))) not (@ad>20020214 or @rlad>20020214)	USPAT;	2003/10/28 14:01
-	10	mask with (stretch\$3 and align\$3) with (substrate or wafer)	US-PGPUB	2003/10/28 14:04
-	0	438/401.ccls. and (mask with (stretch\$3 and align\$3) with (substrate or wafer))	USPAT;	2003/10/28 14:04

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-	10	(mask with (stretch\$3 and align\$3) with (substrate or wafer)) not (@ad>20020214 or @rlad>20020214)	USPAT; US-PGPUB	2003/10/28 14:04
-	1454	mask with (stretch\$3 or align\$3) with (substrate or wafer) and (deposit\$3 with mask)	USPAT; US-PGPUB	2003/10/28 14:08
-	26	438/401.ccls. and (mask with (stretch\$3 or align\$3) with (substrate or wafer) and (deposit\$3 with mask))	USPAT; US-PGPUB	2003/10/28 14:08
-	24	(438/401.ccls. and (mask with (stretch\$3 or align\$3) with (substrate or wafer) and (deposit\$3 with mask))) not (@ad>20020214 or @rlad>20020214)	USPAT; US-PGPUB	2003/10/28 14:17
-	1	"repositionable polymeric aperture mask"	USPAT; US-PGPUB	2003/10/28 14:27
-	14	repositionable with mask	USPAT; US-PGPUB	2003/10/28 14:21
-	13	(repositionable with mask) not (@ad>20020214 or @rlad>20020214)	USPAT; US-PGPUB	2003/10/28 14:19
-	0	"repositionable mask"	USPAT; US-PGPUB	2003/10/28 14:21
-	242879	transistor	USPAT; US-PGPUB	2003/10/28 14:21
-	620	(mask with (stretch\$3 or align\$3) with (substrate or wafer) and (deposit\$3 with mask)) and transistor	USPAT; US-PGPUB	2003/10/28 14:22
-	568	((mask with (stretch\$3 or align\$3) with (substrate or wafer) and (deposit\$3 with mask)) and transistor) not (@ad>20020214 or @rlad>20020214)	USPAT; US-PGPUB	2003/10/28 14:22
-	3	"repositionable aperture mask"	USPAT; US-PGPUB	2003/10/28 14:27
-	0	"repositionable polymeric mask"	USPAT; US-PGPUB	2003/10/28 14:27